

Abstract

The present invention relates to a novel photoresist composition sensitive in the deep ultraviolet region and a method of processing the novel photoresist, where the photoresist comprises a novel copolymer, a photoactive component, and a solvent. The novel copolymer comprises a unit derived from an ethylenically unsaturated compound containing at least one cyano functionality and a unit derived from an unsaturated cyclic non aromatic compound.

0985373E 051101